

Substitute for form 1449A/PTO & 1449B/PTO			Complete if Known	
<b>FIRST          INFORMATION DISCLOSURE          STATEMENT BY APPLICANT</b> <small>(Use as many sheets as necessary)</small>			Application Number	10/764,407
			Filing Date	January 23, 2004
			First Named Inventor	Shenggao Liu et al.
			Examiner Name	
			Attorney Docket Number	005950-844
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FOREIGN PATENT DOCUMENTS												
Examiner Initials	Document Number	Kind Code (if known)	Country	Date of Publication (MM-DD-YYYY)	STATUS							
					Translation	Partial Translation	Eng. Lang. Summary	Search Report	IPER	Abstract	Cited in Spec	
GH GH GH	WO 92/13909		PCT	08/20/92								
	WO 02/058139		PCT	07/25/02								
	WO 02/088077		PCT	11/07/02								

NON-PATENT LITERATURE DOCUMENTS	
Examiner Initials	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
GH	LIANG, Der-Jang, "Synthesis and characterization of new polyamides and polyimides prepared from 2,2-bis[4-(4-aminophenoxy)phenyl]adamantane," <i>Macromol. Chem. Phys.</i> 200. No. 6, pp. 1326-1332 (1999)
GH	NOZAKI, Koji et al., "High-Performance Resist Materials for ArF Excimer Laser and Electron Beam Lithography," <i>FUJITSU Sci Tech. J.</i> , 38, 1, pp. 3-12 (June 2002)
GH	PADMANABAN, Munirathna, et al., "Etch Properties of 193nm Resists: Issues and Approaches," <i>Journal of Photopolymer Science and Technology</i> , Vol 15, No. 3 (2002), pp. 521-528
GH	PADMANABAN, Munirathna, et al., "Layer-Specific Resists for 193nm Lithography," <i>Journal of Photopolymer Science and Technology</i> , Vol. 13, No. 4 (2000) pp. 607-616
GH	PANIEZ, P. J., et al., "Thermal Phenomena in Acrylic 193 nm Resists," <i>SPIE Conferences on Advances in Resist Technology and Processing XVI</i> , Santa Clara, CA, SPIE Vol. 3678 pp. 1352-1363 JUNE 1999 /CH/ 10/1/08
GH	SHIDA, Naomi, "Advanced Materials for 193-nm Resists," <i>Journal of Photopolymer Science and Technology</i> , Vol. 13, No. 4 (2000) pp. 601-606
GH	USHIROGOUCHI, Tohru, et al., "Advanced Materials for 193-nm Resists," In <i>Advances in Resist Technology and Processing XVII</i> , Francis M. Houlihan, Editor, Proceedings of SPIE Vol. 3999 (2000) pp. 1147-1156

Examiner Signature		Date Considered	9/9/05
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\*EXAMINER: Initial preference considered, whether or not citation is in conformance with M.P.E.P. § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.